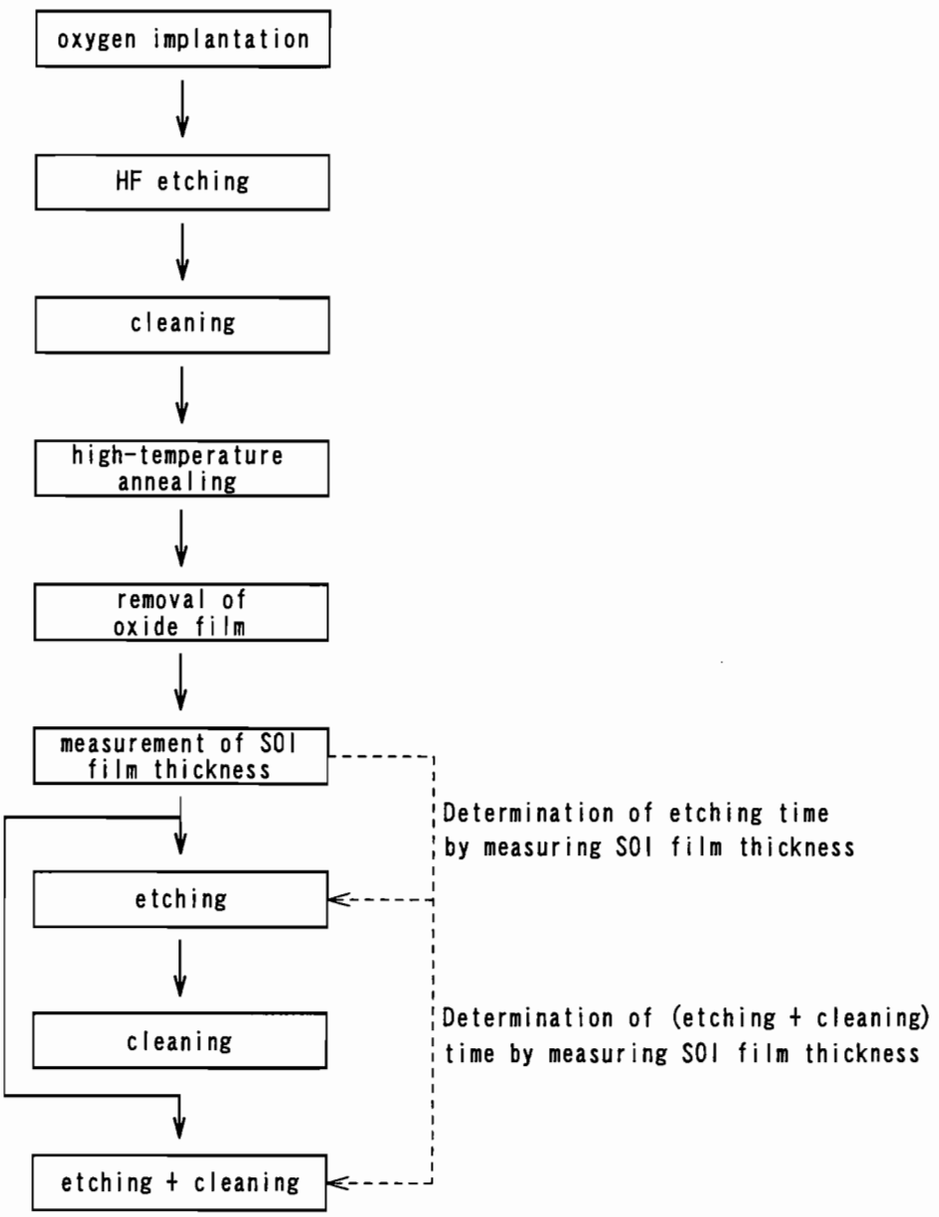
FIG. 1


oxygen implantation
HF etching
cleaning
high-temperature annealing
removal of oxide film
measurement of SOI film thickness
etching
cleaning
etching + cleaning
Determination of etching time by measuring SOI film thickness
Determination of (etching + cleaning) time by measuring SOI film thickness